

PATENT
Docket No.: M4065.0069/P069

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Garo Derderian

Serial No.: 09/121,528

Filed: July 23, 1998

For: CONTINUOUS GOOD STEP
COVERAGE CVD PLATINUM
METAL DEPOSITION

Assistant Commissioner for Patents
Washington, D.C. 20231



Group Art Unit: 1762

Examiner: T. Meeks

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RESPONSE

Dear Sir:

In response to the Office Action dated April 28, 2000 (Paper No. 15), please reconsider the above-identified U.S. patent application in light of the following remarks.

REMARKS

Claims 56-68 stand rejected under 35 U.S.C. §103 as being unpatentable over Baum et al. (U.S. Patent No. 5,783,716). The rejection is respectfully traversed.

The present invention relates to a method for depositing a platinum based metal film by CVD deposition. A non-reactive gas is bubbled over an organic platinum based metal precursor until the non-reactive gas is saturated with the precursor. The platinum based metal film is then deposited onto a substrate in a CVD deposition chamber in the